The diagram illustrates the relative etching depth (in nm) as a function of etching time (in min) for different loads: 10 μN (A), 40 μN (B), and 1.5 μN (C). The etching depth is calculated as \( (A-B) \times 100 \) for the difference between loads A and B. The graph shows the etching behavior over time for the specified loads.